Training Request Form

User Information

Name *
Email *
Registration Status * I have completed the new user registration and turned in the appropriate forms to the UH Nanofabrication Facility’s Administrator.

Training Request


Trainer: Dr. Long Chang
Training Duration: 0.5 hr

Trainer: Dr. Long Chang
Training Duration: 2 hrs
Information: You may bring your sample for the training.

Trainer: Dr. Jing Guo
Training Duration: 0.5 hrs

Trainer: Dr. Jing Guo
Training Duration: 2 hrs
Information: Please specify the material you wish to evaporate in the comment box below.

Trainer: Dr. Long Chang
Training Duration: 2 hrs
Information: Trainees are required to use the equipment within two weeks of training. Please describe your substrate/sample and the patterns you wish to print in the comment box below.

Trainer: Dr. Jing Guo
Training Duration: 1 hr

Trainer: Dr. Jing Guo
Training Duration: 1 to 2 hrs
Information: The FIB is a very versatile machine with many features. We offer three standard training sessions:
1) Scanning Electron Microscopy (2 hrs)
2) Focused Ion Beam (2 hrs)
3) TEM Sample Preparation (up to 6 hrs)
Please specify the type of training you want in the comment box below. Alternatively, you can describe what you want to do and the system administrator will help determine the training you need.

Trainer: Dr. Long Chang
Training Duration: 0.5 hr

Trainer: Dr. Jing Guo
Training Duration: 1 hr

Trainer: Dr. Jing Guo
Training Duration: 1 to 2 hrs
Information: The equipment supports 2.5”x2.5”, 4”x4”, or 5”x5” square masks. Please describe your substrate dimensions and the smallest features you want to print in the comment box below.

Information: Please watch the video located on the Nanofab Inventory Database computer.

Trainer: Dr. Jing Guo
Training Duration: 1 hr

Information: No training is required to use the optical microscopes. Please ask a staff or other users if you need instructions.

Trainer: Dr. Jing Guo
Training Duration: 0.5 hr

Trainer: Dr. Jing Guo
Training Duration: 1 to 2 hrs
Information: The RTP contains the following process gas: Ar, O2, N2

Trainer: Dr. Long Chang
Training Duration: 1 hr
Information: The RIE 100 system contains the following process gas: Ar, O2
Please describe what you plan to etch in the comment box below.

Trainer: Dr. Long Chang
Training Duration: 1 hr
Information: The RIE180 system contains the following process gas: Ar, O2, SF6, C4F8, CHF3, He, H
We do not allow milling of metals in this system. Please describe what you plan to etch in the comment box below.

Trainer: Dr. Long Chang
Training Duration: 1 hr
Information: The RIE 80 system contains the following process gas: Ar, O2, SF6, CHF3, CF4
Please describe what you plan to etch in the comment box below.

Trainer: Dr. Jing Guo
Training Duration: 2 hrs

Trainer: Dr. Jing Guo
Training Duration: 0.5 hr

Trainer: Dr. Jing Guo
Training Duration: 1 to 2 hrs
Information: The spin coater supports only 3” wafers, 4” wafers or at least 1 cm x 1 cm chip.

Trainer: Dr. Jing Guo
Training Duration: 2 hrs
Information: Users are required to purchase their own targets to use in the UHV Sputtering System. Please specify the materials you want to deposit in the comment box below.

Information: There is no training required to operate the vacuum ovens. Please follow the Standard Operating Procedure (SOP) located near the ovens. You must submit this form before you are permitted to reserve the vacuum ovens.

Bad Time *
(Please specify times when you will not be available for training in the box.)

Describe what you need this instrument for *